

Amendments to the Specification:

Please replace paragraph beginning at page 8, line 20 with the following amended paragraph:

Thereafter, a passivation film 6 is formed in the passivation step of Figure 6. This completes the fabrication of the NRD guide in which the dielectric-B film 4 surrounding by the dielectric-A film 3 and sandwiched by the conductive films 2 and 5 functions as the transmission line. As shown in Figures 1-6, the substrate 1 may include a MEMS circuit 11 previously formed therein. In this embodiment, the portion in which an air layer is formed in a conventional NRD guide is filled with the dielectric-A film 3. The dielectric-B film 4 is formed using a material having a larger dielectric constant than that of the dielectric-A film 3; if the dielectric constant difference is made large, a wave having any wavelength in the millimeter to submillimeter wave regions can be transmitted.